

Sputtering Pt on Si using Sputter#4

Sputtering Condition: 3mT, 50W (439v), Ar=45sccm, z=2.75, tilting=5, and time=360 s

Result: the sputtering rate≈3.9nm/min, roughness Ra=0.402nm.

Figure 1 Film Thickness=23.6nm.

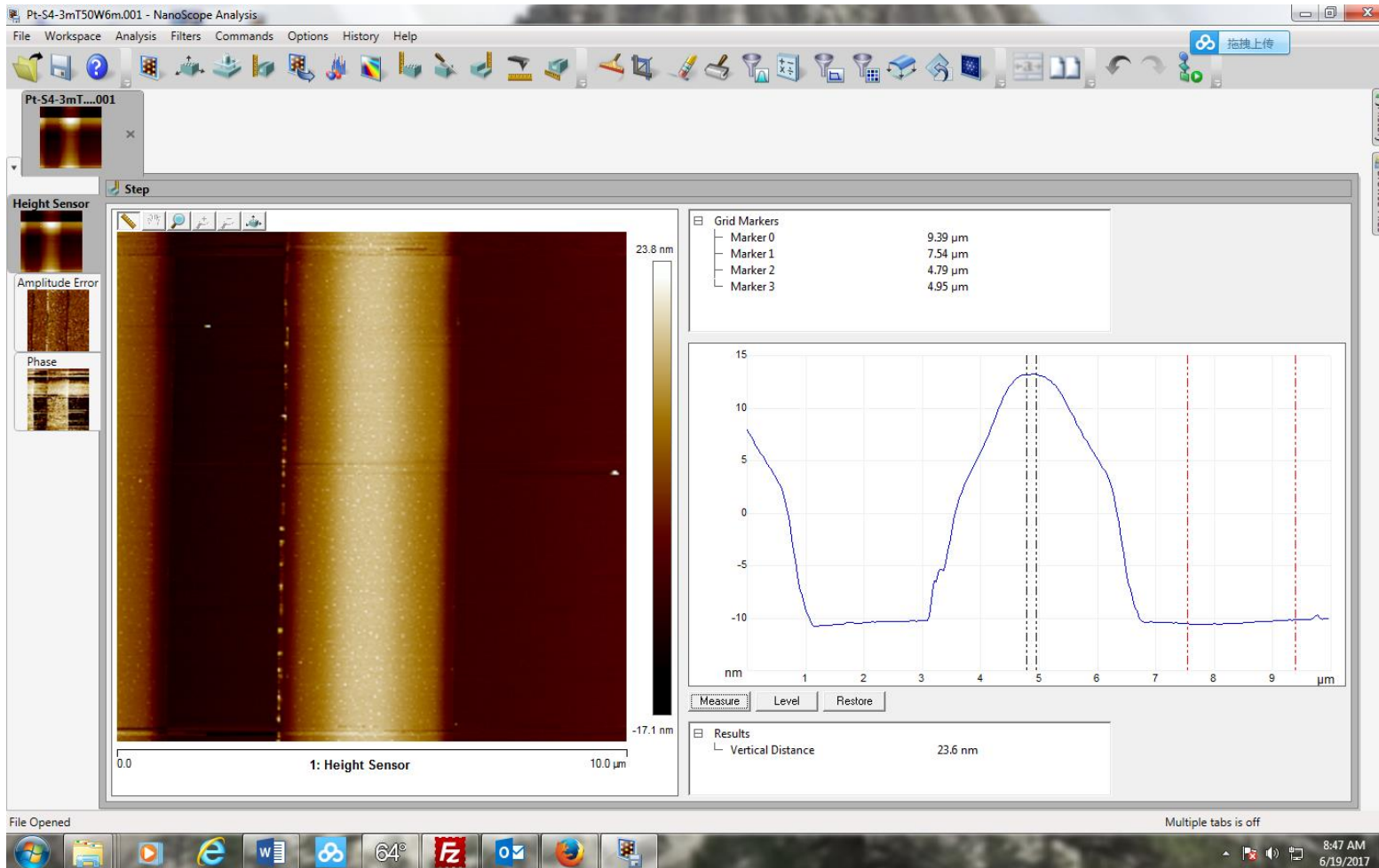


Figure 2 Surface scan by AFM (Ra=0.402 nm).

